



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Zhu et al.

Attorney Docket No.:
NOVLP090/NVLS-002888

Application No.: 10/733,858

Examiner: Smith, Bradley

Filed: December 10, 2003

Group: 2891

Title: BIASED H₂ ETCH PROCESS IN
DEPOSITION-ETCH-DEPOSITION GAP
FILL

Confirmation No. 7860

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as first-class mail on June 20, 2006 in an envelope addressed to the Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450.

Signed

Tara Hayden

**INFORMATION DISCLOSURE STATEMENT
BEFORE FINAL ACTION OR NOTICE OF ALLOWANCE
(37 CFR §§ 1.56 AND 1.97(c))**

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

The references listed in the attached PTO Form 1449, a copy of which is attached, may be material to examination of the above-identified patent application. Applicants submit this reference in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make this citation of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that this reference indeed constitutes prior art.

This Information Disclosure Statement is being filed after the mailing date of the first Office Action on the merits, or after three months of the filing date of this application, whichever event occurred last, but it is believed before the mailing date of either: (i) a final action under §1.113 or (ii) a notice of allowance under §1.311, whichever occurs first.

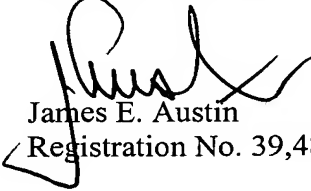
Accompanying this Information Disclosure Statement is

- ☐ a statement as specified in 37 CFR 1.97(e); or
- ☒ the fee set forth in 37 CFR 1.17(p).

If fees are due, enclosed is our Check No. 1278 for \$180.00 in payment of the Information Disclosure Statement Fee. If it is determined that any additional fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 500388 (Order No. NOVLP090).

Respectfully submitted,

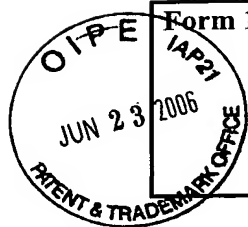
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Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No. NOVLP090/NVLS-2888 Applicant: Zhu et al. Filing Date December 10, 2003	Application No.: 10/733,858 Group 2891
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U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A1	6,812,043	11.2004	Bao et al.			
	A2	6,821,905 B2	11.2004	Pan et al.			
	A3	2003/0203652 A1	10.2003	Bao et al.			
	A4	2004/0110390 A1	06.2004	Takagi et al.			
	A5	2005/0250346 A1	11.2005	Schmitt			
	A6	2005/0130411 A1	06.2005	Bao et al.			
	A7	6,486,081 B1	11.2002	Ishikawa et al.			
	A8	6,211,065 B1	04.2001	Xi et al.			

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	C1	U.S. Office Action mailed December 14, 2005, from U.S. Application No. 10/728,569. [Atty Dckt. NOVLP087/NVLS-2880]
	C2	Nguyen et al., "Halogen-Free Noble Gas Assisted H ₂ Plasma Etch Process in Deposition-Etch-Deposition Gap Fill", Novellus Systems, Inc., filed March 1, 2006, Application No. Not yet assigned. [Atty Dkt No. NOVLP149/NVLS-3129].
	C3	U.S. Office Action mailed February 16, 2006, from U.S. Application No. 11/082,369. [Atty Dckt. NOVLP129/NVLS-3055]
	C4	U.S. Office Action mailed June 1, 2006, from U.S. Application No. 10/728,569. [Atty Dckt. NOVLP087/NVLS-2880]
Examiner		Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.